

# NARROW GAP ELECTRONEGATIVE CAPACITIVE DISCHARGES AND STOCHASTIC HEATING

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Motivation: widely used for thin film etch and deposition

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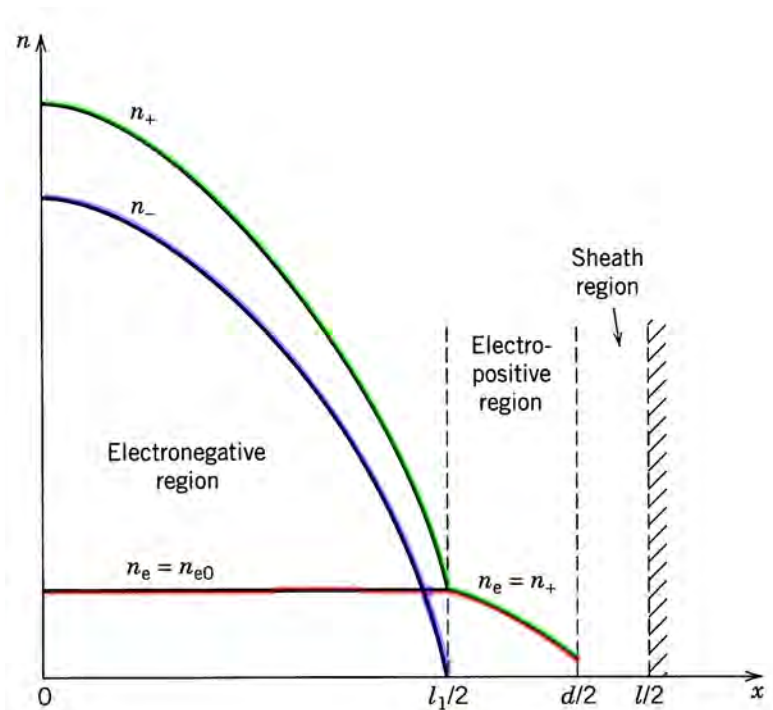
<http://www.eecs.berkeley.edu/~lieber>

# OUTLINE

- Narrow gap oxygen discharges
  - PIC simulations
  - Equilibrium discharge model
- Stochastic (collisionless) heating
  - Narrow gap oxygen
  - Two-step density model with argon
  - Ohmic heating issues
  - Single-step with finite slope

# DISCHARGE CONFIGURATION

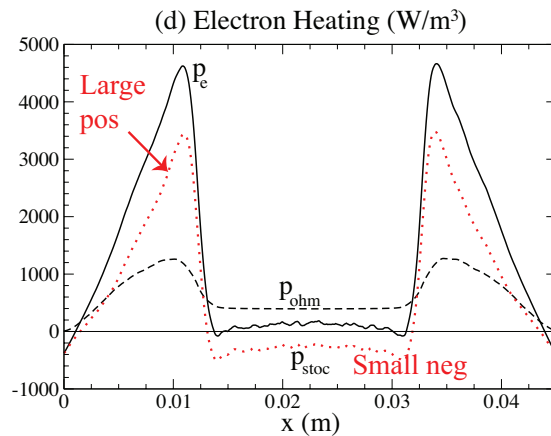
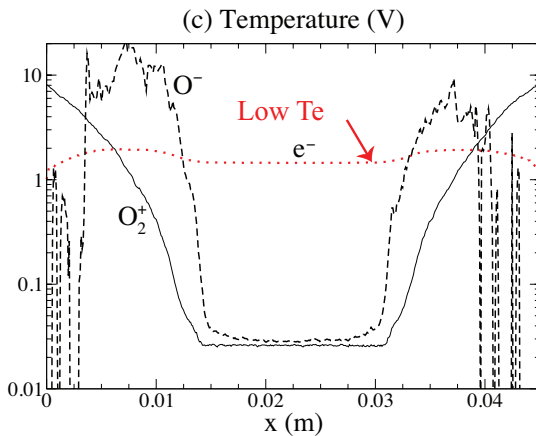
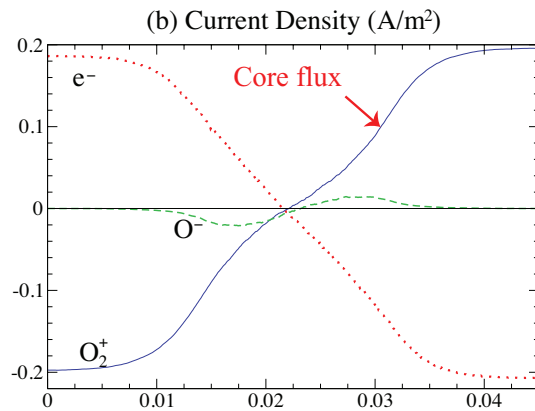
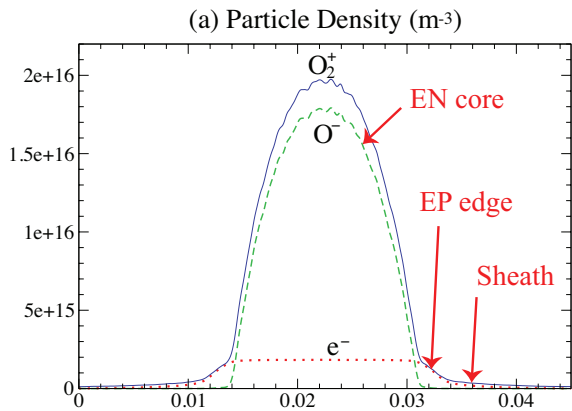
- Oxygen at 10–100 mTorr,  $V_{\text{rf}} = 500\text{--}2000\text{ V}$
- 1D plane-parallel geometry ( $\sim 1\text{--}10\text{ cm}$  gap length  $L$ )
- Usual model is stratified discharge with electronegative (EN) core and electropositive (EP) edge



- As  $L$  is decreased, the EP edge can disappear and new interesting phenomena are found

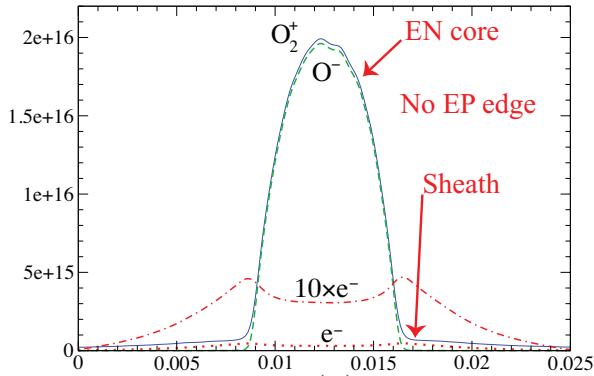
**PIC SIMULATIONS AND EQUILIBRIUM MODELING**  
(Vary gap length  $L$  at  $p=50$  mTorr,  $V_{\text{rf}} = 500$  V)

# L=4.5 cm (EP EDGE EXISTS)

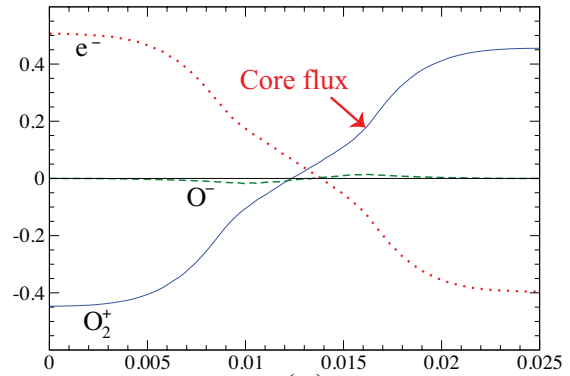


# L=2.5 cm (NO EP EDGE)

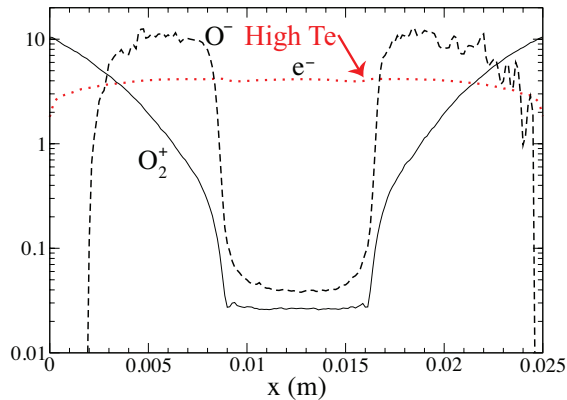
(a) Particle Density ( $\text{m}^{-3}$ )



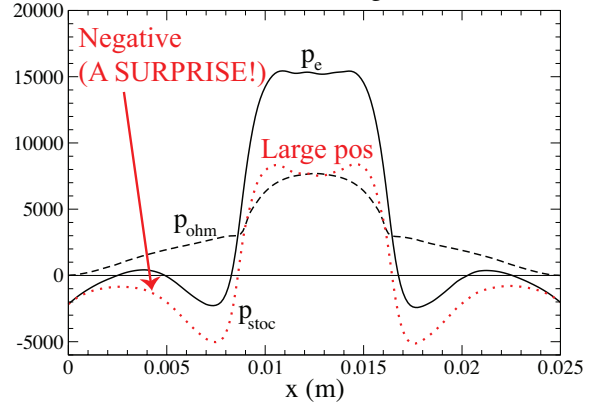
(b) Current Density ( $\text{A/m}^2$ )



(c) Temperature (V)

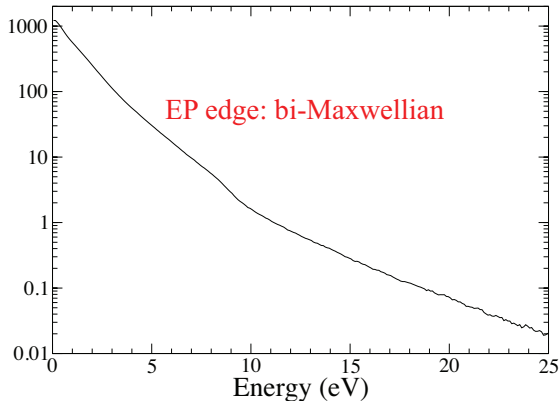


(d) Electron Heating ( $\text{W/m}^3$ )

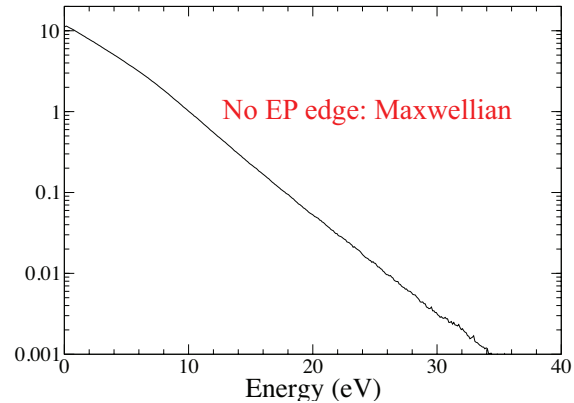


# EEDF'S AND DENSITY DETAILS

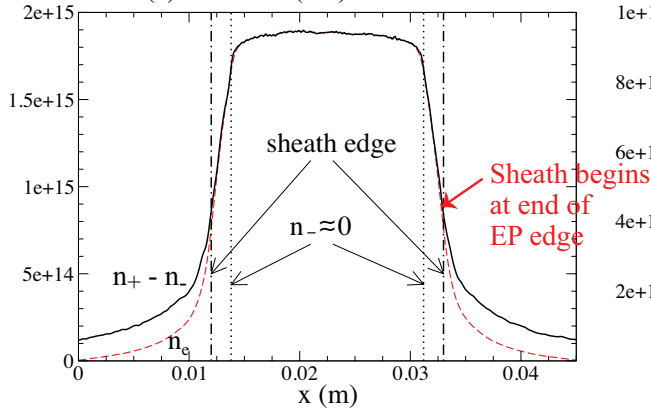
(a) EEDF (a.u.) for  $L = 4.5$  cm



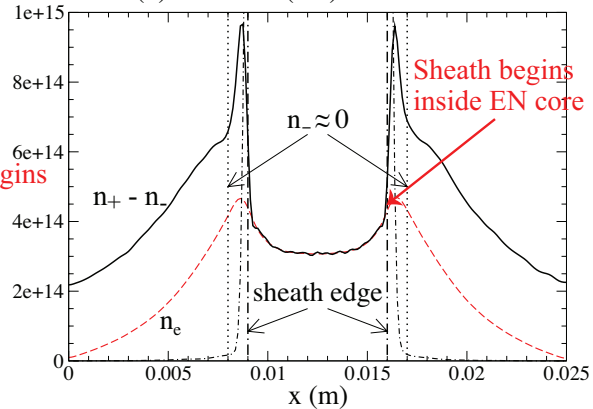
(b) EEDF (a.u.) for  $L = 2.5$  cm



(a) Densities ( $\text{m}^{-3}$ ) for  $L = 4.5$  cm

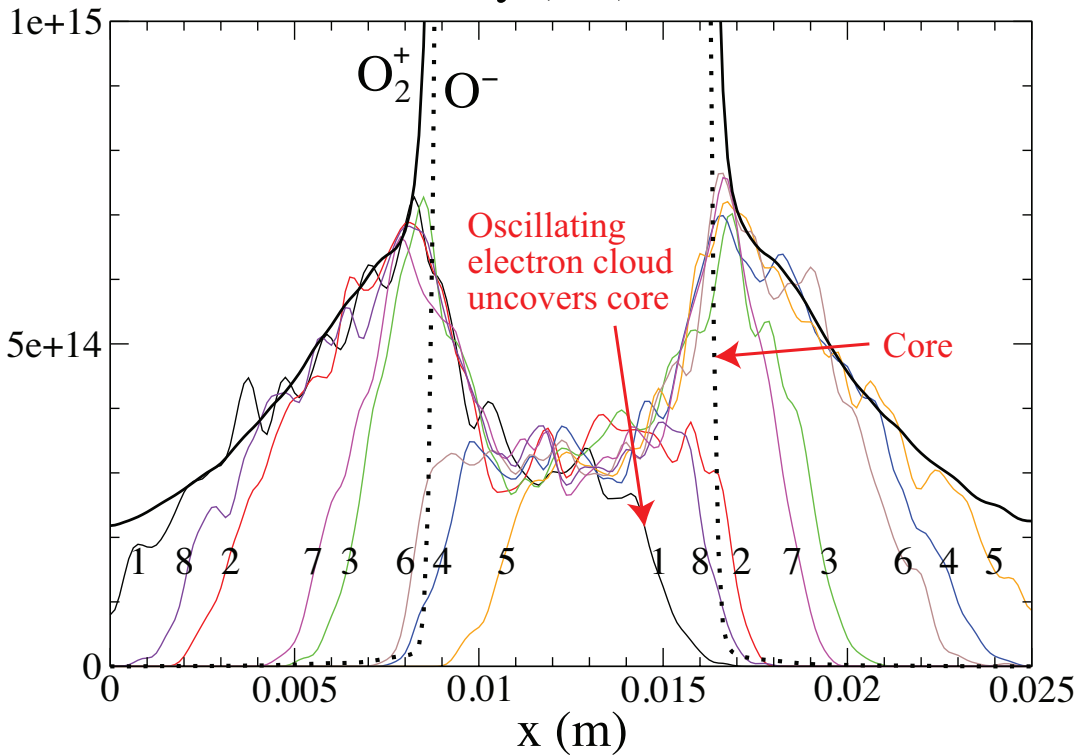


(b) Densities ( $\text{m}^{-3}$ ) for  $L = 2.5$  cm



# TIME-VARYING DENSITY (L=2.5 cm, NO EP EDGE)

Electron density ( $\text{m}^{-3}$ ) at T/8 intervals



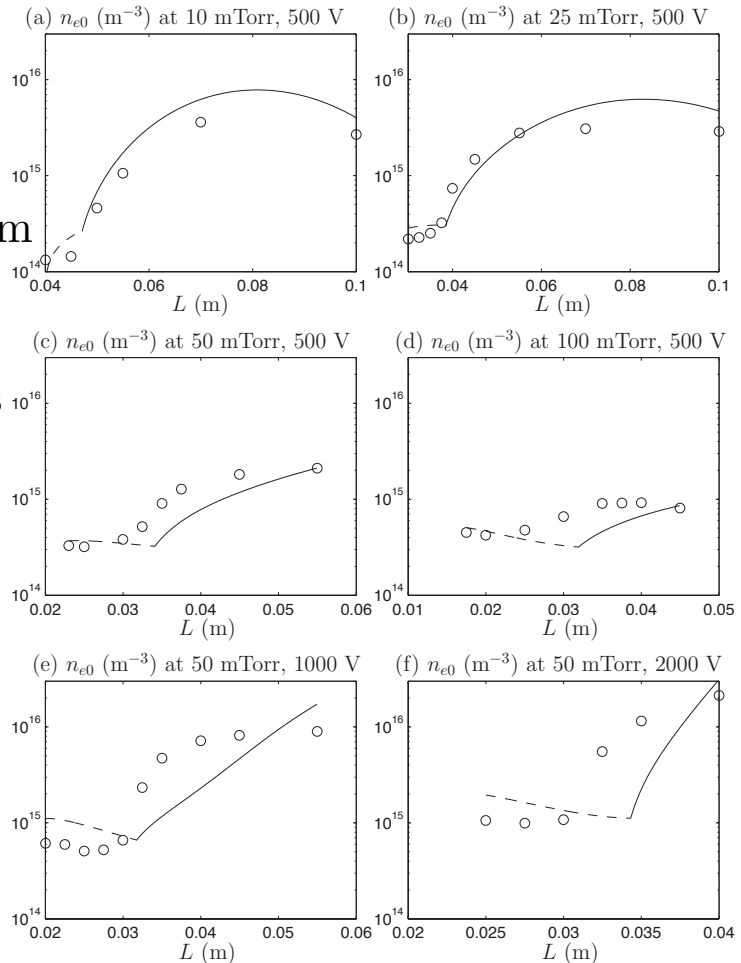


# MODELING CONSIDERATIONS

- EP edge exists (larger gap lengths  $L$ )
  - Bi-Maxwellian EEDF
  - About half the ion flux generated in sheath/EP edge
  - Usual Child law rf sheath
  - Usual positive collisionless heating in sheath
- No EP edge (smaller gap lengths  $L$ )
  - Maxwellian EEDF
  - Over half the ion flux generated in sheath
  - Attachment in sheath is important
  - Unusual rf sheath containing negative ions
  - Negative collisionless heating in sheath, positive in core
- Models developed:
  - model with some inputs from PIC results
  - self-consistent model

# MODEL WITH SOME INPUTS FROM PIC

- Rate coefficients and collisional energy losses using PIC EEDF
- Power deposition in core from PIC results
- Solid lines (2-region model with EP edge); Dashed lines (1-region model without EP edge); circles (PIC results)
- Reasonable agreement between model and PIC results (submitted to Physics of Plasmas, 2013)

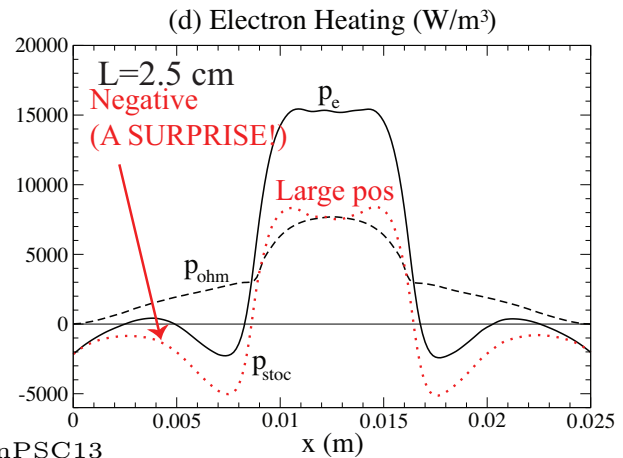
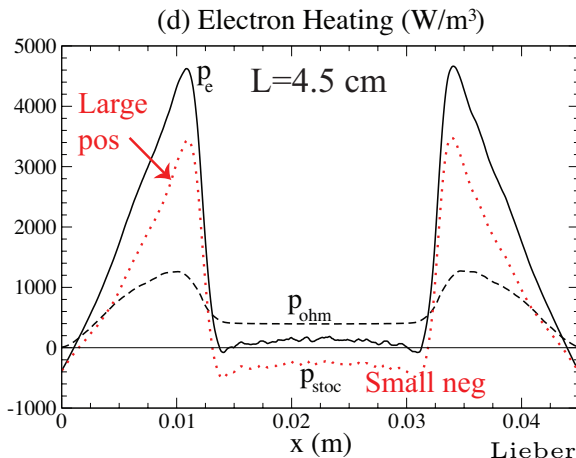
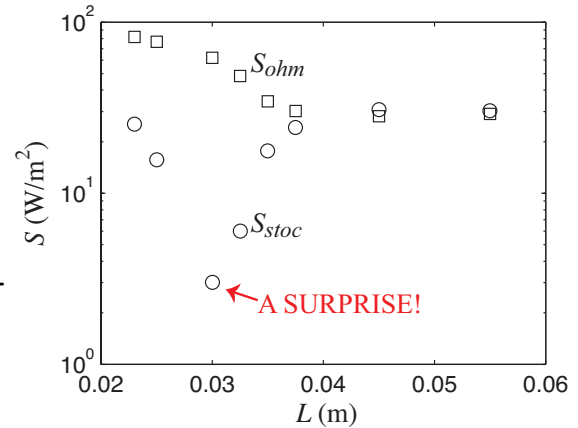


# STOCHASTIC (COLLISIONLESS) HEATING

(WORK IN PROGRESS)

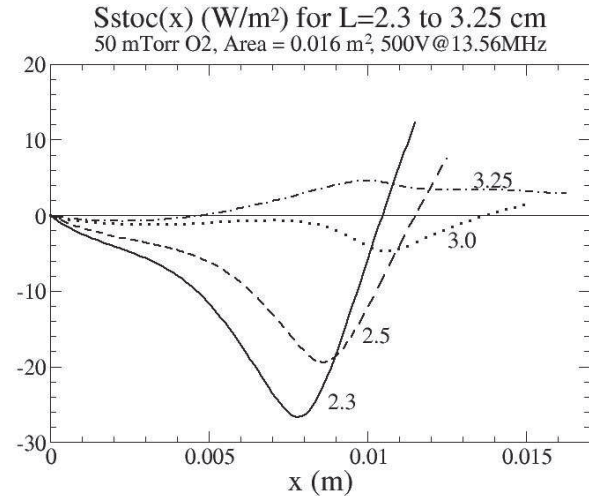
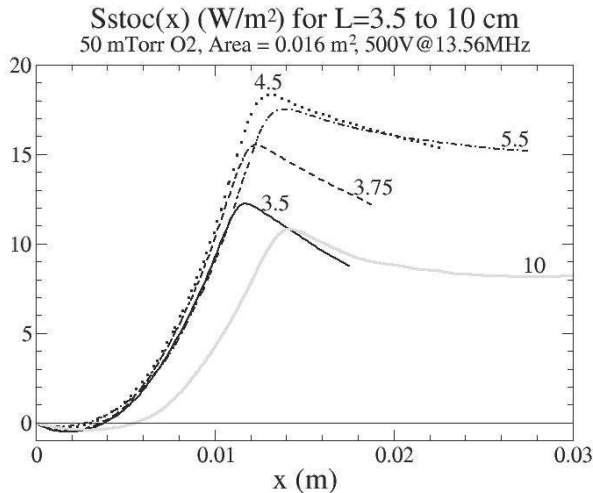
# PIC RESULTS FOR VARIOUS GAPS L (50 mT, 500 V)

- Stochastic heating small at transition where EP edge disappears
- EP edge exists  $\Rightarrow$  positive heating in sheath, negative in core
- No EP edge  $\Rightarrow$  negative heating in sheath, positive in core



## $S_{\text{stoc}}(x)$ FOR VARIOUS GAPS $L$

- Integrate  $p_{\text{stoc}}(x)$  from electrode ( $x = 0$ ) toward discharge midplane  $\Rightarrow S_{\text{stoc}}(x)$



- Large  $L \Rightarrow n_e(\text{core}) > n_e(\text{sheath})$   
 $\Rightarrow$  positive heating in sheath, negative heating in core
- Small  $L \Rightarrow n_e(\text{sheath}) > n_e(\text{core})$   
 $\Rightarrow$  negative heating in sheath, positive heating in core

## TWO-STEP DENSITY MODEL

1. I.D. Kaganovich, Phys. Rev. Lett. **89**, 265006 (2002).
2. E. Kawamura, M.A. Lieberman and A.J. Lichtenberg, Phys. Plasmas **13**, 053506 (2006).

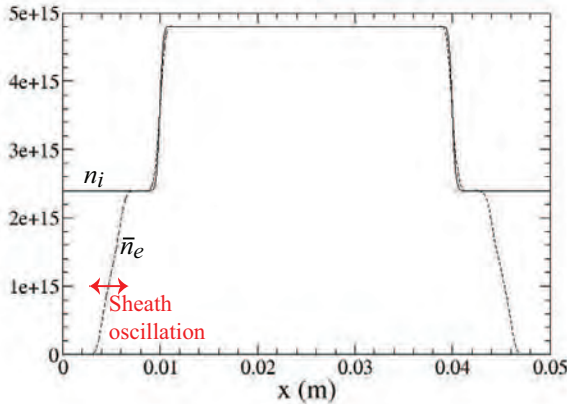
Use to investigate stochastic heating

# FIXED IONS, PIC ELECTRONS (30 mT Ar, 13.56 MHz)

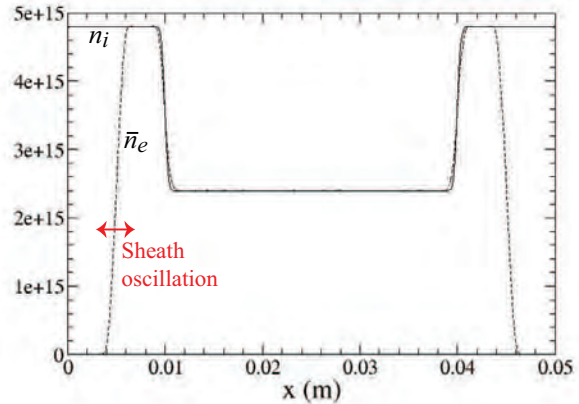
(Models EN plasma with EP edge)

(Models EN plasma with no EP edge)

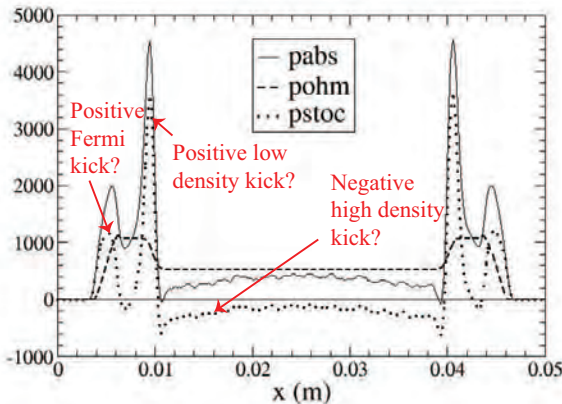
Plasma Density ( $\text{m}^{-3}$ )



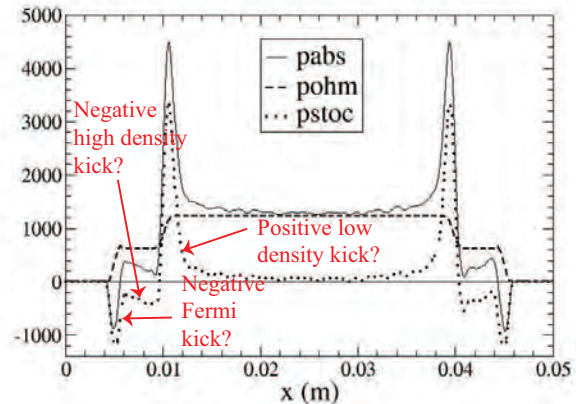
Plasma Density ( $\text{m}^{-3}$ )



Electron Heating ( $\text{W}/\text{m}^3$ )



Electron Heating ( $\text{W}/\text{m}^3$ )

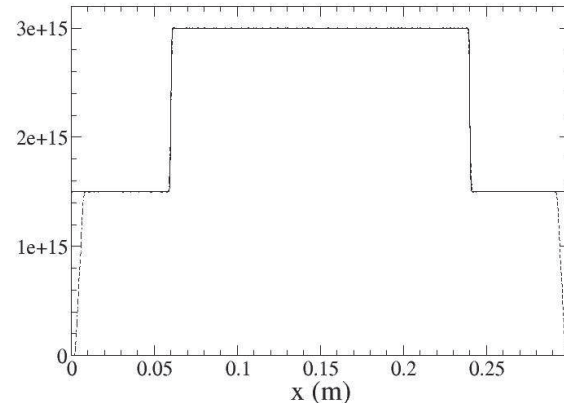


# ELECTRON HEATING GAS PRESSURE EFFECTS

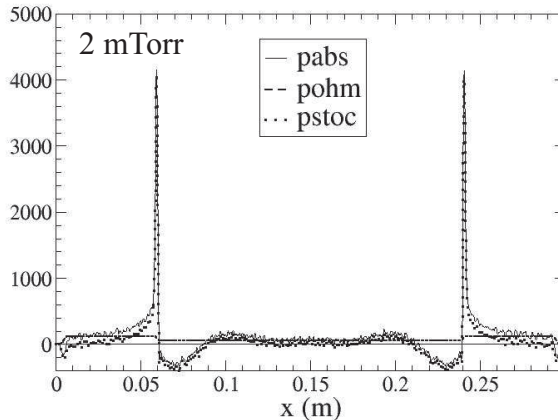
- Large device
- 2:1 step at 6 cm
- At 2 mT 66% of heating is ohmic; at 30 mT 96% is ohmic

⇒ error in finding stochastic heating

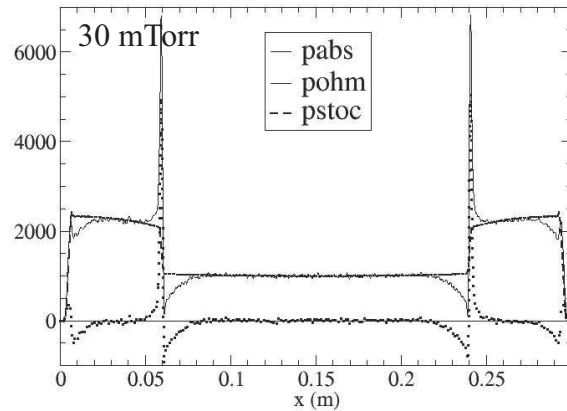
Plasma Density ( $\text{m}^{-3}$ )



Electron Heating ( $\text{W}/\text{m}^3$ )



Electron Heating ( $\text{W}/\text{m}^3$ )





# PIC SIMULATION OHMIC HEATING ISSUES

(see Lister, Li and Godyak, 1996)

- Ohmic power density  $p_{\text{ohm}} = \frac{1}{2} |J_{\text{rf}}|^2 \text{Re}[1/(\sigma_p + j\omega\epsilon_0)]$ , where

$$\sigma_p = -\frac{4\pi e^2}{3m} \int_0^\infty \frac{v^3 dv}{j\omega + \nu_m(v)} \frac{df_{e0}}{dv}$$

- The usual simple expression (see Margenau, 1946)

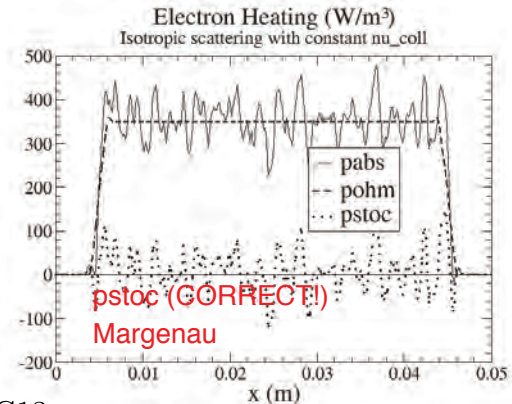
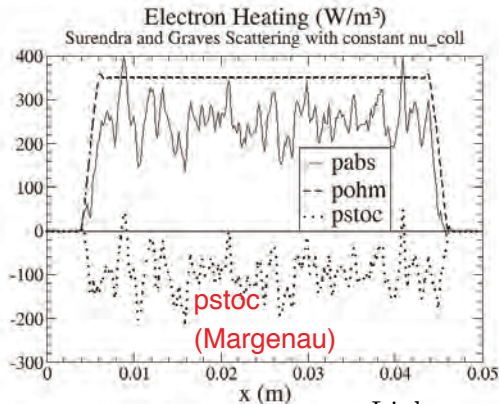
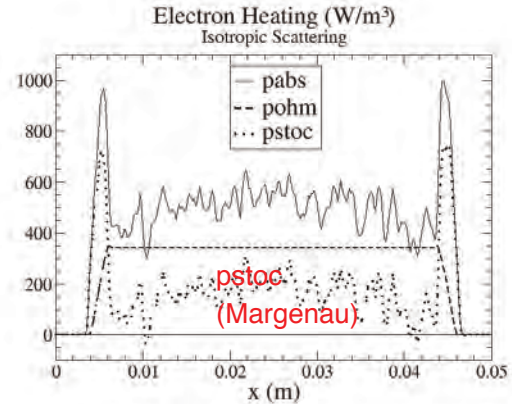
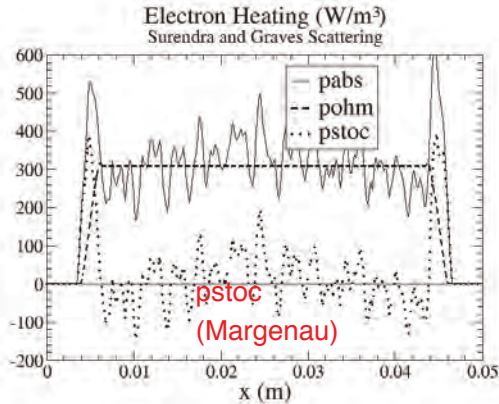
$$\sigma_p = \frac{e^2 n_e}{m(j\omega + \nu_m)}$$

is not correct unless  $\nu_m = \text{const}$

- Argon is a Ramsauer gas with  $\nu_m$  a function of  $v$
- The momentum transfer frequency  $\nu_m$  must be distinguished from the “total” collision frequency  $\nu_{\text{coll}}$
- Large errors in calculating stochastic heating for ohmic heating  $\gg$  stochastic heating
- Can use “pseudo-argon” in PIC simulation  $\Rightarrow \nu_m = \nu_{\text{coll}} = \text{const}$

# VARIOUS COLLISION MODELS (UNIFORM PLASMA)

Fixed Ion Uniform 5 mTorr Argon with  $n_b = 4.8e15 \text{ m}^{-3}$   
 $V_{rf}=1000 \text{ V}$ ,  $f=13.56 \text{ MHz}$ ,  $L=0.05 \text{ m}$ ,  $\text{Area}=0.01 \text{ m}^2$

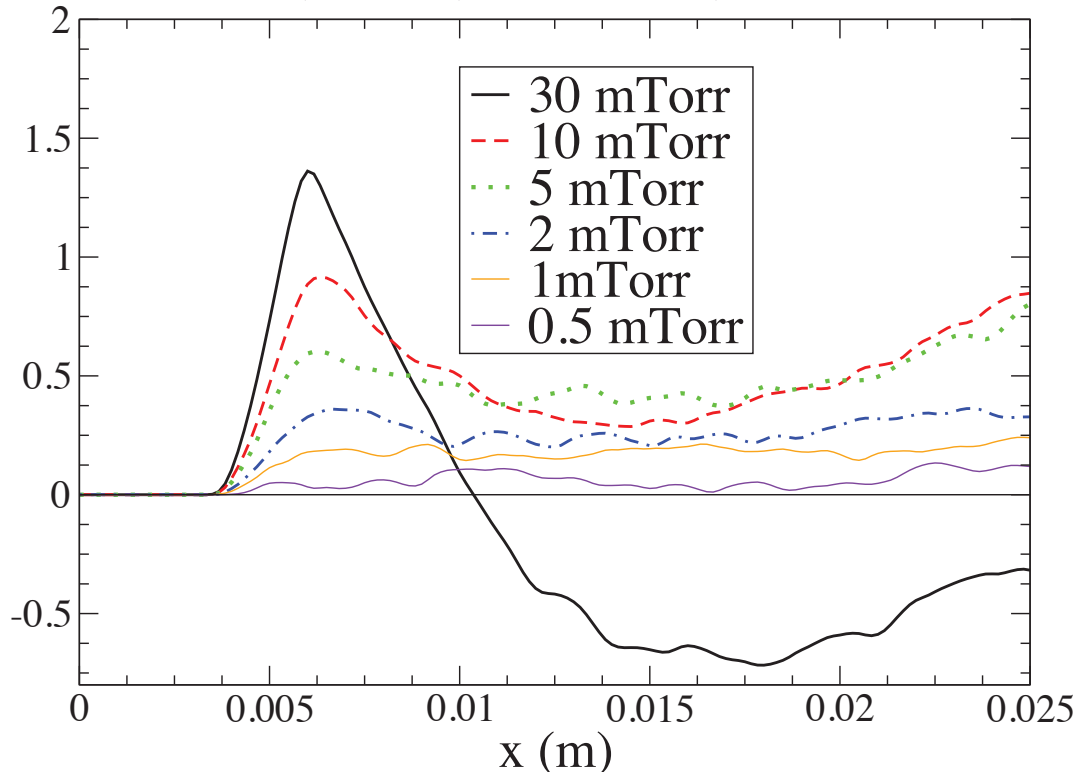


# STOCHASTIC HEATING (5 CM UNIFORM PLASMA)

(Ramsauer elastic cross section, non-isotropic scattering)

$S_{stoc}(x)$  ( $W/m^2$ ) for Uniform Profiles

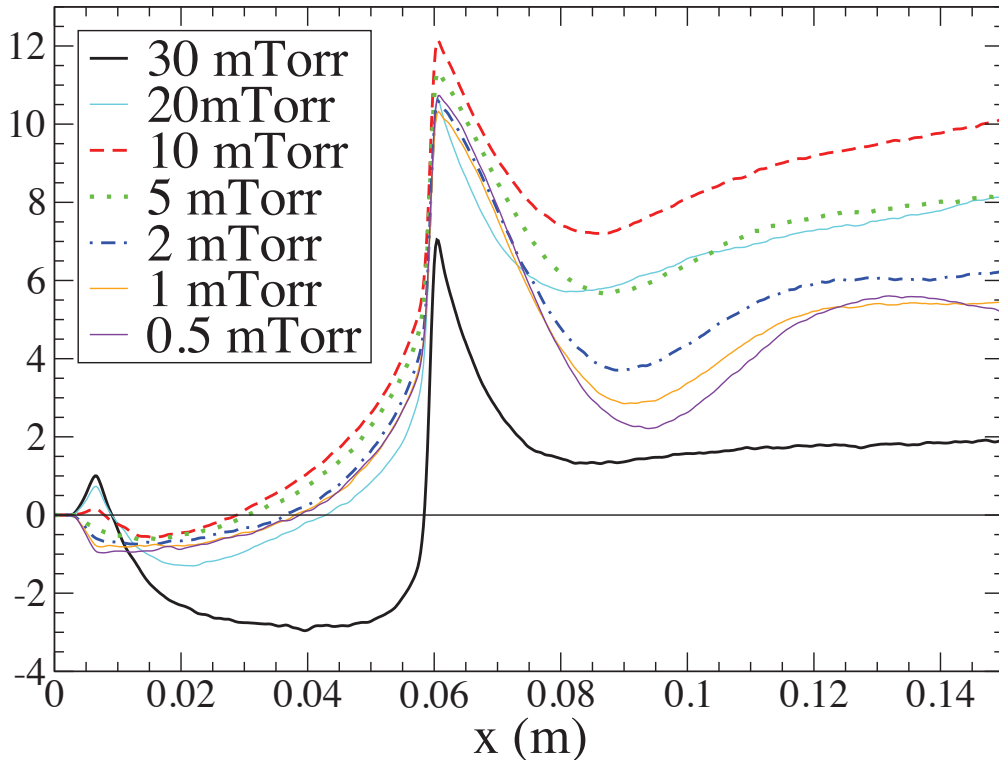
0-30 mTorr Ar,  $L=5$  cm, Area =  $0.01$   $m^2$ ,  $1000V@13.56MHz$



# STOCHASTIC HEATING (2:1 STEP, $d_{\text{edge}} = 6$ CM)

(Ramsauer elastic cross section, non-isotropic scattering)

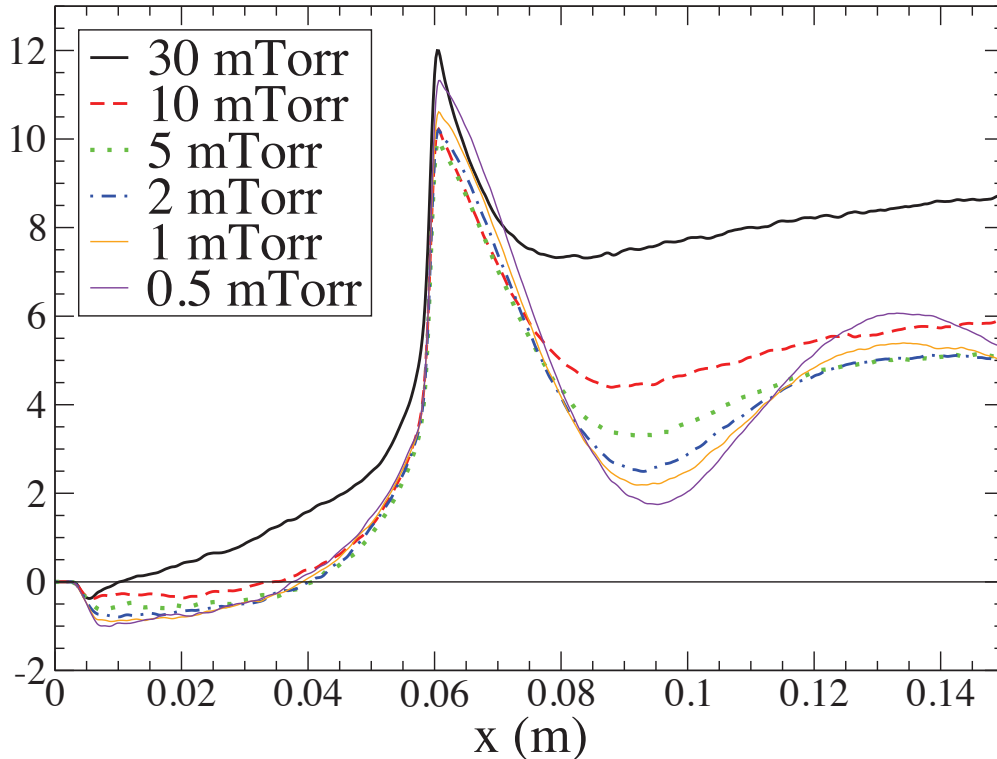
$S_{\text{stoc}}(x)$  ( $\text{W}/\text{m}^2$ ) for  $d_{\text{edge}} = 6$  cm,  $v_{\text{coll}}(x)$   
2-30 mTorr Ar,  $L = 30$  cm, Area =  $0.01$   $\text{m}^2$ ,  $0.41\text{A}$  @  $13.56\text{MHz}$



# STOCHASTIC HEATING (2:1 STEP, $d_{\text{edge}} = 6$ CM)

(Constant collision frequency, isotropic scattering)

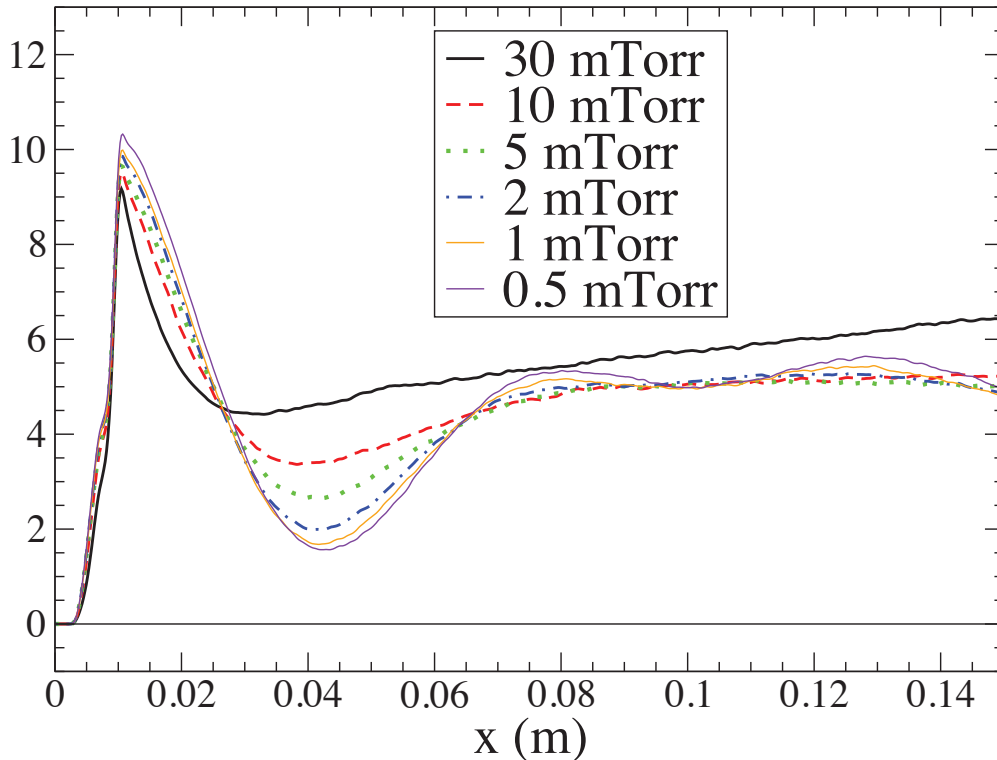
$S_{\text{stoc}}(x)$  ( $\text{W}/\text{m}^2$ ) for  $d_{\text{edge}} = 6$  cm, Iso., const  $K_{\text{el}}$   
0.5-30 mTorr Ar,  $L = 30$  cm, Area =  $0.01$   $\text{m}^2$ ,  $0.41\text{A}$  @  $13.56\text{MHz}$



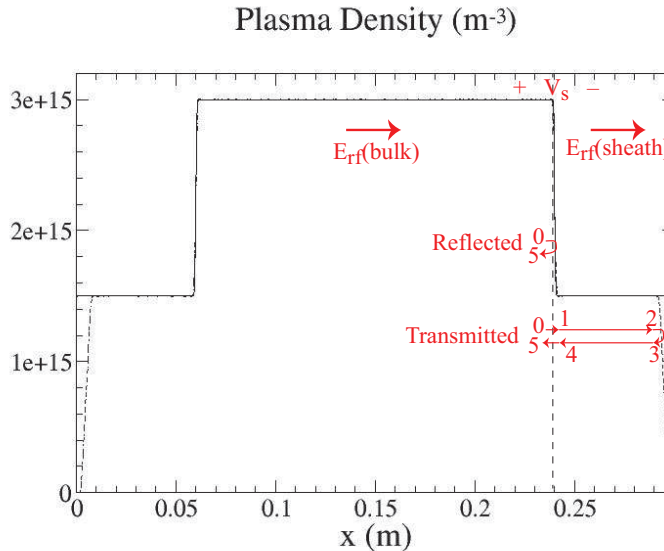
# STOCHASTIC HEATING (2:1 STEP, $d_{\text{edge}} = 1$ CM)

(Constant collision frequency, isotropic scattering)

$S_{\text{stoc}}(x)$  ( $\text{W}/\text{m}^2$ ) for  $d_{\text{edge}} = 1$  cm, Iso., const  $K_{\text{el}}$   
0.5-30 mTorr Ar,  $L = 30$  cm, Area =  $0.01$   $\text{m}^2$ ,  $0.41\text{A}$  @  $13.56\text{MHz}$



# ENERGY KICK FOR TWO-STEP DENSITY



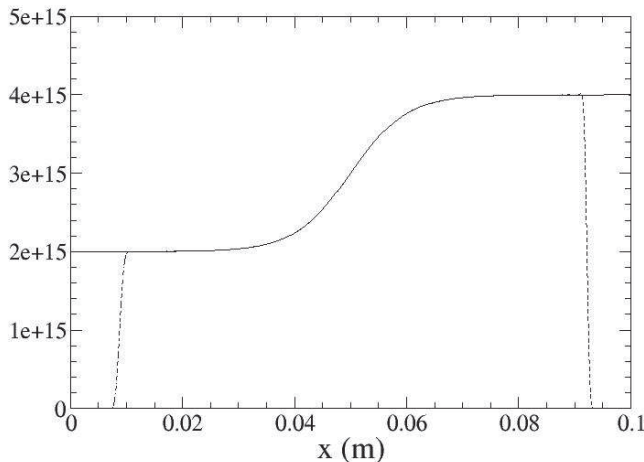
- There is a potential drop  $V_s = T_e \ln(n_b/n_s)$  across the step
- There are rf fields  $E_{\text{rf}}(\text{bulk})$  and  $E_{\text{rf}}(\text{sheath})$
- Calculate the phase-averaged energy kick  $\Delta \mathcal{E}$  for transmitted and reflected particles
- There is no contribution to the kick at the oscillating plasma-sheath edge ( $2 \rightarrow 3$ )

# SINGLE STEP WITH VARIABLE SLOPE (PIC)

30 mTorr Argon fixed Ion Tanh profile with  $a_1=10$  to 400,  $a_2=3$ ,  $n_l/n_r=0.5$ ,  
 $I_{rf}=0.3$  A,  $f=27.12$  MHz,  $L=0.1$  m, Area=0.01 m<sup>2</sup>,  $n_l=2e15$  m<sup>-3</sup>

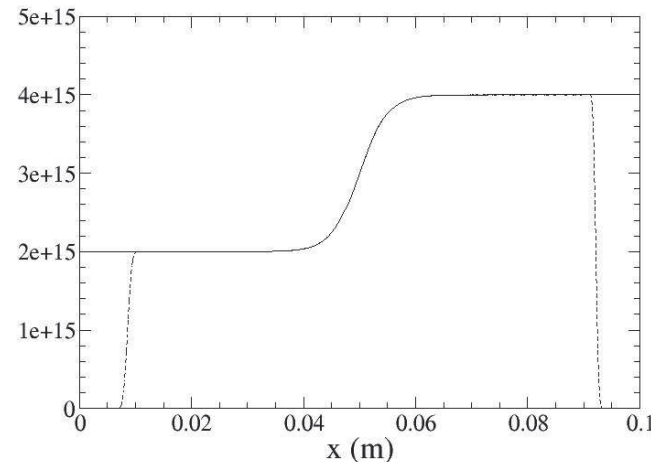
(a)  $a_1 = 10$

Plasma Density (m<sup>-3</sup>)



(b)  $a_1 = 20$

Plasma Density (m<sup>-3</sup>)

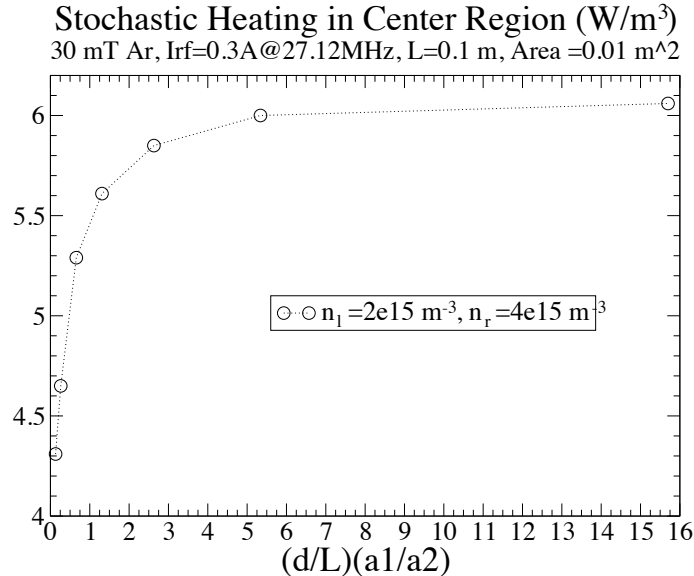


$$n(x) = \frac{n_0}{2} \left[ a_2 + \tanh \left( \frac{a_1}{L} \left( x - \frac{L}{2} \right) \right) \right]$$

- Vary slope using  $a_1$  in tanh function and find stochastic heating



# STOCHASTIC HEATING WITH VARIABLE SLOPE



- $d = v_e/\omega \approx 0.4\text{ cm} =$  “mixing” length (1 radian phase change) ( $v_e =$  electron thermal velocity)
- $La_2/a_1 =$  scale length of step (0.025–3 cm)
- Saturation for small scale length; adiabatic for large scale length
- Electron oscillation amplitude ( $\approx 0.04\text{ cm}$ ) may be significant

# SUMMARY

- A transition from a narrow gap EN discharge with an EP edge, to a narrower gap discharge with no EP edge, was investigated with PIC simulations and modeling
- The effects of a bi-Maxwellian EEDF, with an EP edge, and sheath attachment and core uncovering, with no EP edge, need to be taken into account in modeling
- A transition from sheath to internal stochastic heating after the EP edge disappears is observed, and is being studied with fixed ion, two-step and single-step density, PIC simulations
- At the higher pressures, the ohmic heating has to be carefully calculated in order to determine the true stochastic heating in the PIC simulations